



UNIVERSITI PUTRA MALAYSIA

**STABILITY OF THIN LIQUID FILM UNDER EFFECT
OF APOLAR AND ELECTROSTATIC FORCES ON
A HORIZONTAL PLANE**

MOHANAD M-A. A. EL-HARBAWI

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ELECTROSTATIC FORCES ON A HORIZONTAL PLANE**

By

MOHANAD M-A. A. EL-HARBAWI

**Thesis Submitted to the School of Graduate Studies, Universiti Putra Malaysia,
in Fulfilment of the Requirements for Degree of Master of Science**

August 2002



DEDICATED

TO

My parents, brothers and sisters for their real help



Abstract of thesis presented to the Senate of Universiti Putra Malaysia in fulfillment of the requirement for the degree of Master of Science

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MOHANAD M-A. A. EL-HARBAWI

August 2002

Chairman: Dr. Sa'ari Mustapha

Faculty: Engineering

The understanding of stability, dynamics and morphology of supported thin ($<100nm$) liquid films and nanodrops are important in phenomena like flotation, adhesion of fluid particles to surfaces, kinetics and thermodynamics of precursor films in wetting, heterogeneous nucleation, film boiling/condensation, multilayer adsorption/film pressure, instability of biological films/membranes, and many other areas. While the wetting of surface by large drops is relatively well understood, wetting characteristics of nanodrops and films have not been extensively studied. In some applications like trickle bed reactors, thick coating, contact equipment for heat and mass transfer, and the like

Factors that would affect the total free excess energy (per unit area) of a thin film on a substrate include the film thickness, as well as the apolar and electrostatic spreading coefficients for the system. The dynamics of the liquid film is formulated using the Navier-Stokes equations augmented by a body forces describing the apolar

and electrostatic interactions. The liquid film is assumed to be charge neutralized, nondraining, and laterally unbounded. A modified Navier-Stokes equation with associated boundary conditions is solved using a long wave approximation method to obtain a nonlinear equation of evolution of the film interface.

A nonlinear theory based upon the condition of infinitesimal perturbation on the film surface is derived to obtain the growth coefficient, dominant wavelength (i.e., wavelength corresponding to maximum growth coefficient of the surface instability) and the film rupture time.

Solution of the nonlinear partial differential equation for a wide range of the initial amplitude and wavelength is solved by using finite difference methods. The calculation domain is fixed on the interval $0 < X < 2\pi/\lambda$. The mesh size is taken sufficiently small so that space and time errors are negligible. The nonlinear algebraic equations obtained as a result of finite difference discretization are solved using efficient-numerical technique employing IMSL subroutine DNEQNJ.

The electrostatic force part is bigger in value than apolar, therefore it found that it plays the dominant role in characteristics of thin films and the main effect on the behavior of the excess free energy, growth rate, maximum growth rate, neutral wave, dominant wavenumber, dominant wavelength and rupture time. The linear theory may overestimate or underestimate the time of rupture by several orders of magnitude depending upon thin film parameters. Hence linear theory is inadequate to describe the stability characteristics of films and therefore, the need of a nonlinear

approach to the study of thin film dynamics. The calculations indicated that the apolar and electrostatic forces can be solely responsible for the formation of flat film of $h_0 \cong 30\text{nm}$ in thickness. In this respect the proposed theory is consistent with the effect of apolar and electrostatic forces on thin liquid films on a horizontal plane.

Abstrak tesis yang dikemukakan kepada Senat Universiti Putra Malaysia sebagai memenuhi keperluan untuk ijazah Master Sains

**KESTABILAN SAPUT CECAIR NIPIS DI BAWAH KESAN DAYA APOLAR
DAN ELEKTROSTATIK PADA SATU PERMUKAAN RATA**

Oleh

MOHANAD M-A. A. EL-HARBAWI

Ogos 2002

Pengerusi: Dr. Sa'ari Mustapha

Fakulti: Kejuruteraan

Kefahaman berkenaan kestabilan, Dinamik dan morfologi bagi cecair filem nipis ($<100nm$) dan titisan nano adalah mustahak dalam fenomena seperti perapungan, pelekatan cecair bendalir ke permukaan, kinetik dan termodinamik penanda filem dalam pembasahan, penukleusan heterogen, pendidihan/pemelewapan, pelbagai lapisan penjeraban/tekanan filem, ketidakstabilan filem biologi/membran, dan banyak bidang lain. Sementara pembasahan permukaan oleh titisan besar adalah mudah di fahami, pencirian pembasahan titisan nano dan filem belum dikaji secara intensif. Dalam beberapa penggunaan seperti reaktor lapisan cucur, bersalut tebal, peralatan sentuh bagi haba dan pemindahan jisim, dan sebagainya.

Filem berkenaan adalah dimodelkan sebagai dua dimensi cecair Newtonian ketumpatan tetap ρ dan kelikatan μ mengalir pada satah mendatar. Cecair filem ketebalan min h_0 , adalah dianggap nipis cukup untuk mengabaikan kesan graviti dan



terhad diatas oleh satu gas dan terlanjut secara sisi ke infinit (model dua-dimensi). Kemudian aliran seperti berikut boleh diwakili oleh satu persamaan dua-dimensi Navier-stokes dipasangkan dengan persamaan selanjar dan keadaan sempadan bersekutu. Sebutan daya badan dalam persamaan Navier-stokes adalah diubahsuai dengan memasukkan saling tindak antara molekul berlebihan (apolar dan daya elektrostatik) antara filem bendalir dan permukaan pepejal dipunyai daya apolar dan daya elektrostatik. Persamaan Navier-Stokes terkait dengan keadaan sempadan bersekutu adalah telah diselesaikan di bawah kaedah anggaran gelombang panjang untuk mendapat satu persamaan tidak linear bagi filem antara muka.

Satu teori tidak linear berdasarkan atas keadaan usikan sangat kecil ke atas permukaan filem adalah diterbitkan untuk mendapat pekali pertumbuhan, panjang gelombang berkaitan kepada pekali pertumbuhan maksimum bagi ketidakstabilan permukaan dan masa filem pecah.

Persamaan tidak linear bagi eolusi adalah diselesaikan secara berangka dalam bentuk konservatif sebagai sebahagian satu masalah nilai awal bagi keadaan sempadan berkata sempadan pada banjaran tertetap $0 < X < 2\pi/\lambda$, dimana λ adalah satu gelombang angka. Perbezaan tertengah dalam ruang dan peraturan takat tengah (crank-Nicholson) dalam masa digunakan. Saiz jejaring adalah diambil cukup kecil dengan itu ralat ruang dan ralat masa diabaikan. Persamaan algebra tidak linear diperolehi sebagai satu hasil pengdiskretan perbezaan terhingga adalah diselesaikan menggunakan teknik berangka cepat menggunakan IMSL subroutin DNEQNJ.

Bahagian daya elektrostatik adalah lebih besar dalam nilai, apolar, dengan itu kita dapati iaitu ia memainkan peranan penting dalam pencirian filem nipis dan kesan utama ke atas tingkahlaku tenaga bebas berlebihan, kadar tumbuh maksimum, gelombang neutral, gelombang nombor dominan, panjang gelombang dominan dan masa pecah. Teori linear mungkin terlebih anggaran atau terkurang anggaran masa pecah oleh beberapa tertib magnitud bergantung atas parameter filem nipis. Dengan itu teori linear adalah tidak cukup untuk menghurai ciri kestabilan filem dan dengan itu, keperluan satu pendekatan tidak linear kepada kajian bagi dinamik filem nipis. Pengiraan menunjukkan daya apolar dan daya elektrostatik mungkin hanya bertanggungjawab bagi pembentukan filem flat no $h_0 \cong 30 \text{ nm}$ ketebalan. Dalam hal ini teori cadangan adalah konsisten dengan kesan daya apolar dan daya elektrostatik ke atas filem cecair nipis pada satu satah mendatar.

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Sa'ari Mustapha, Ph.D.

Associate Professor
Faculty of Engineering
Universiti Putra Malaysia
(Chairman)

Azni Idris, Ph.D.

Associate Professor
Faculty of Engineering
Universiti Putra Malaysia
(Member)

Chuah Teong Guan, Ph.D.

Faculty of Engineering
Universiti Putra Malaysia
(Member)

AINI IDERIS, Ph.D.

Professor/Dean
School of Graduate Studies
Universiti Putra Malaysia

Date:



TABLE OF CONTENTS

		Page
DEDICATION		ii
ABSTRACT		iii
ABSTRAK		vi
ACKNOWLEDGEMENTS		ix
APPROVAL		x
DECLARATION		xii
LIST OF TABLE		xiii
LIST OF FIGURES		xvii
LIST OF SYMBOLS		xxii
 CHAPTER		
I	INTRODUCTION	1
	Scope of the Study	4
	Object of the Study	4
 II	 LITERATURE REVIEW	 6
	Applications of Thin Liquid Films In Biomedical Science	16
	Intermolecular Forces in Thin Liquid Films	19
	Lifshitz-Van der Waals (Apolar) Forces	21
	Electrostatic Double Layer Interaction (Electrostatic Forces)	25
 III	 INSTABILITY AND MORPHOLOGY OF APOLAR AND ELECTROSTATIC FORCE	 32
	The Nonlinear Equation for Dynamics of Thin Film	32
	Hydrodynamic Model and Governing Equation	32
	Scaling of the Hydrodynamic Equations	35
	Long Wave Approximation	37
	Component of The Surface Free Energy and Forces Due to Intermolecular Interactions	44
	Intermolecular Forces in Thin Films	44
	Excess Free Energy for the Film	49
	Linear Stability Theory	52
 IV	 NUMERICAL SOLUTION OF THE NONLINEAR EVOLUTION EQUATION	 53
 V	 RESULTS AND DISCUSSION	 56
	Comparison between Apolar and Electrostatic Forces	56
	Results from Linear Theory	57
	Results from Nonlinear Simulation	59
	Comparison of Prediction from Nonlinear and Linear Theories	61
	Effect of the Amplitude of Disturbance on the Rupture	70
	Depiction of the Growth of Instability (Film Profile) Time	74
 VI	 CONCLUSION	 77



VII	RECOMMENDATIONS	81
	REFERENCES	82
	APPENDIX A	93
	APPENDIX B	103
	APPENDIX C	117
	BIODATA OF THE AUTHOR	125



LIST OF TABLES

Table		Page
A1.	Growth rate as function of h_0 at $\lambda = (0.01 - 0.1)$ from linear theory.	93
A2.	Growth rate as function of h_0 at $\lambda = (0.1 - 1.0)$ from linear theory.	93
A3.	Growth rate as function of wavelength at $h_0 = (2 - 30)nm$ from linear theory.	94
A4.	Rupture time as a function of wavenumber at $h_0 = 2$ from linear and nonlinear theories and $\varepsilon = 0.5$.	95
A5.	Rupture time as a function of wavenumber at $h_0 = 4$ from linear and nonlinear theories and $\varepsilon = 0.5$.	95
A6.	Rupture time as a function of wavenumber at $h_0 = 6$ from linear and nonlinear theories and $\varepsilon = 0.5$.	95
A7.	Rupture time as a function of wavenumber at $h_0 = 8$ from linear and nonlinear theories and $\varepsilon = 0.5$.	96
A8.	Rupture time as a function of wavenumber at $h_0 = 10$ from linear and nonlinear theory and $\varepsilon = 0.5$.	96
A9.	Rupture time as a function of wavenumber at $h_0 = 20$ from linear and nonlinear theories and $\varepsilon = 0.5$.	96
A10.	Rupture time as a function of wavenumber at $h_0 = 30$ from linear and nonlinear theories and $\varepsilon = 0.5$.	97
A11.	Rupture time as a function of wavenumber at $h_0 = 2$ from linear and nonlinear theories and $\varepsilon = 0.9$.	97
A12.	Rupture time as a function of wavenumber at $h_0 = 4$ from linear and nonlinear theories and $\varepsilon = 0.9$.	97
A13.	Rupture time as a function of wavenumber at $h_0 = 6$ from linear and nonlinear theories and $\varepsilon = 0.9$.	98
A14.	Rupture time as a function of wavenumber at $h_0 = 8$ from linear and nonlinear theories and $\varepsilon = 0.9$.	98



A15.	Rupture time as a function of wavenumber at $h_0 = 10$ from linear and nonlinear theories and $\varepsilon = 0.9$.	98
A16.	Rupture time as a function of wavenumber at $h_0 = 20$ from linear and nonlinear theories and $\varepsilon = 0.9$.	99
A17.	Rupture time as a function of wavenumber at $h_0 = 30$ from linear and nonlinear theory and $\varepsilon = 0.9$.	99
A18.	Rupture time as a function of wavenumber at $h_0 = 200 \text{ nm}$ from linear and nonlinear theory and $\varepsilon = 0.9$.	99
A19.	Ratio of rupture time as a function of wavelength at $h_0 = (2 - 30) \text{ nm}$ and $\varepsilon = 0.5$.	100
A20.	Ratio of rupture time as a function of wavelength at $h_0 = (2 - 30) \text{ nm}$ and $\varepsilon = 0.9$.	100
A21.	Rupture time as function of amplitude of perturbation at $h_0 = 5 \text{ nm}$, $\lambda = 0.1$ and $\omega = 0.0870$.	101
A22.	Rupture time as function of amplitude of perturbation at $h_0 = 10 \text{ nm}$, $\lambda = 0.1$ and $\omega = 0.0048$.	101
A23.	Rupture time as function of amplitude of perturbation at $h_0 = 15 \text{ nm}$, $\lambda = 0.1$ and $\omega = 1.0\text{E-}4$.	101
A24.	Rupture time as function of amplitude of perturbation at $h_0 = 20 \text{ nm}$, $\lambda = 0.1$ and $\omega = 2.0\text{E-}6$.	102
A25.	Rupture time as function of amplitude of perturbation at $h_0 = 25 \text{ nm}$, $\lambda = 0.1$ and $\omega = 2.0\text{E-}8$.	102
A26.	Rupture time as function of amplitude of perturbation at $h_0 = 30 \text{ nm}$, $\lambda = 0.1$ and $\omega = 3.0\text{E-}10$.	102
A27.	Rupture time as function of amplitude of perturbation at $h_0 = 5 \text{ nm}$, $\lambda = 0.9$ and $\omega = 7.0499$.	103
A28.	Rupture time as function of amplitude of perturbation at $h_0 = 10 \text{ nm}$, $\lambda = 0.9$ and $\omega = 0.3903$.	103
A29.	Rupture time as function of amplitude of perturbation at $h_0 = 15 \text{ nm}$, $\lambda = 0.9$ and $\omega = 9.0\text{E-}3$.	103

- A30. Rupture time as function of amplitude of perturbation at 104
 $h_0 = 20 \text{ nm}$, $\lambda = 0.9$ and $\omega = 1.0\text{E-}4$.
- A31. Rupture time as function of amplitude of perturbation at 104
 $h_0 = 25 \text{ nm}$, $\lambda = 0.9$ and $\omega = 2.0\text{E-}6$.
- A32. Rupture time as function of amplitude of perturbation at 104
 $h_0 = 30 \text{ nm}$, $\lambda = 0.9$ and $\omega = 2.0\text{E-}8$.



LIST OF FIGURES

Figure		Page
1	Electrical potential distribution in an interacting double layer between two identical slabs.	26
2	A small rectangular element in a fluid is shown. The pressure forces in the z -direction act on the surface of area A . The electrical body forces are proportional to the volume ($A \Delta z$).	27
3	Schematic presentation of interfacial instability of thin fluid, 3 bounded by a substrate, 1 and a semi-infinite fluid, 2.	34
4	The relationship between h_0 and the components of free energies, ($\Delta G'^w$ & $\Delta G''$).	57
5	Growth rate as function of h_0 at $\lambda = (0.01 - 0.1)$ from linear theory.	58
6	Growth rate as function of h_0 at $\lambda = (0.1 - 1.0)$ from linear theory.	59
7	Growth rate as function of wavelength at $h_0 = (2 - 30)nm$ from linear theory.	60
8	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 2$ & $\varepsilon = 0.5$.	62
9	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 4$ & $\varepsilon = 0.5$.	63
10	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 6$ & $\varepsilon = 0.5$.	63
11	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 8$ & $\varepsilon = 0.5$.	64
12	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 10$ & $\varepsilon = 0.5$.	64
13	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 20$ & $\varepsilon = 0.5$.	65



14	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 30$ & $\varepsilon = 0.5$.	65
15	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 200nm$ & $\varepsilon = 0.9$.	66
16	Ratio of rupture time as function of wavelength at $h_0 = 2nm$ & $\varepsilon = 0.5$.	67
17	Ratio of rupture time as function of wavelength at $h_0 = 4nm$ & $\varepsilon = 0.5$.	68
18	Ratio of rupture time as function of wavelength at $h_0 = 6nm$ & $\varepsilon = 0.5$.	68
19	Ratio of rupture time as function of wavelength at $h_0 = 8nm$ & $\varepsilon = 0.5$.	69
20	Ratio of rupture time as function of wavelength at $h_0 = 10nm$ & $\varepsilon = 0.5$.	69
21	Ratio of rupture time as function of wavelength at $h_0 = 20nm$ & $\varepsilon = 0.5$.	70
22	Ratio of rupture time as function of wavelength at $h_0 = 30nm$ & $\varepsilon = 0.5$.	70
23	Rupture time as function of amplitude of perturbation at $h_0 = 5nm$ and $\lambda = 0.1$.	71
24	Rupture time as function of amplitude of perturbation at $h_0 = 10nm$ and $\lambda = 0.1$.	72
25	Rupture time as function of amplitude of perturbation at $h_0 = 15nm$ and $\lambda = 0.1$.	72
26	Rupture time as function of amplitude of perturbation at $h_0 = 20nm$ and $\lambda = 0.1$.	73
27	Rupture time as function of amplitude of perturbation at $h_0 = 25nm$ and $\lambda = 0.1$.	73
28	Rupture time as function of amplitude of perturbation at $h_0 = 30nm$ and $\lambda = 0.9$.	74
29	Film profile at different times for $\varepsilon = 0.5$ and $h_0 = 4nm$. The rupture proceeds explosively at $t_n = 0.0084$.	75
30	Film profile at different times for $\varepsilon = 0.5$ and $h_0 = 8nm$. The rupture proceeds explosively at $t_n = 0.0174$.	76



31	Film profile at different times for $\varepsilon = 0.5$ and $h_0 = 10\text{ nm}$. The rupture proceeds explosively at $t_n = 0.4018$.	75
B1	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 2\text{ nm}$ & $\varepsilon = 0.9$.	104
B2	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 4\text{ nm}$ & $\varepsilon = 0.9$.	104
B3	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 6\text{ nm}$ & $\varepsilon = 0.9$.	105
B4	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 8\text{ nm}$ & $\varepsilon = 0.9$.	105
B5	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 10\text{ nm}$ & $\varepsilon = 0.9$.	106
B6	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 20\text{ nm}$ & $\varepsilon = 0.9$.	106
B7	A comparison of rupture times for linear and nonlinear theories as functions of wavenumber, λ , at $h_0 = 30\text{ nm}$ & $\varepsilon = 0.9$.	107
B8	Ratio of rupture time as function of wavelength at $h_0 = 2\text{ nm}$ & $\varepsilon = 0.9$	108
B9	Ratio of rupture time as function of wavelength at $h_0 = 4\text{ nm}$ & $\varepsilon = 0.9$	108
B10	Ratio of rupture time as function of wavelength at $h_0 = 6\text{ nm}$ & $\varepsilon = 0.9$.	109
B11	Ratio of rupture time as function of wavelength at $h_0 = 8\text{ nm}$ & $\varepsilon = 0.9$.	109
B12	Ratio of rupture time as function of wavelength at $h_0 = 10\text{ nm}$ & $\varepsilon = 0.9$.	110
B13	Ratio of rupture time as function of wavelength at $h_0 = 20\text{ nm}$ & $\varepsilon = 0.9$.	110
B14	Ratio of rupture time as function of wavelength at $h_0 = 30\text{ nm}$ & $\varepsilon = 0.9$.	111
B15	Rupture time as function of amplitude of perturbation at $h_0 = 5\text{ nm}$ and $\lambda = 0.1$.	112
B16	Rupture time as function of amplitude of perturbation at $h_0 = 10\text{ nm}$ and $\lambda = 0.1$.	112



B17	Rupture time as function of amplitude of perturbation at $h_0 = 15 \text{ nm}$ and $\lambda = 0.1$.	113
B18	Rupture time as function of amplitude of perturbation at $h_0 = 20 \text{ nm}$ and $\lambda = 0.1$.	113
B19	Rupture time as function of amplitude of perturbation at $h_0 = 25 \text{ nm}$ and $\lambda = 0.1$.	114
B20	Rupture time as function of amplitude of perturbation at $h_0 = 30 \text{ nm}$ and $\lambda = 0.1$.	114
B21	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 4 \text{ nm}$. The rupture proceeds explosively at $t_n = 0.001$ and $n = 21$.	115
B22	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 10 \text{ nm}$. The rupture proceeds explosively at $t_n = 0.0316$ and $n = 21$.	115
B23	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 20 \text{ nm}$. The rupture proceeds explosively at $t_n = 50.8125$ and $n = 21$.	116
B24	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 4 \text{ nm}$. The rupture proceeds explosively at $t_n = 0.0099$ and $n = 41$.	116
B25	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 10 \text{ nm}$. The rupture proceeds explosively at $t_n = 0.0312$ and $n = 41$.	117
B26	Film profile at different times for $\varepsilon = 0.9$ and $h_0 = 4 \text{ nm}$. The rupture proceeds explosively at $t_n = 50.8110$ and $n = 41$.	117

LIST OF SYMBOLS

A	Area	m^2
A'	Hamakar constant	-
A'_y	Hamakar constant for various binary interactions	-
Ca	Capillary number	-
d_0	Equilibrium separation distance between two bulks phase at contact	nm
$H(h)$	Thickness of thin film	nm
h_0	Mean thickness of thin film	nm
k	Debye length	nm
L	Distance from the surface	nm
L_0	Equilibrium distance	nm
$P(p)$	Hydrodynamic pressure inside the film	Kpa
P_0	Pressure in the film	Kpa
q	Nondimensional wavenumber (a small parameter) used for rescaling space and time coordinates	-
S^{LW}	apolar component of spreading coefficient of the film liquid	mJ/m^2
R	Radius of a sphere	cm
$T(t)$	Time coordinate	-
t_l	Rupture time from linear theory	sec
t_n	Rupture time from nonlinear theory	-
$U(u)$	x -Component of the velocity vector	- (m/s)



$W(w)$	z -Component of the velocity vector	- (m/s)
$X(x)$	Spatial coordinate in the longitude direction	- (m)
$Z(z)$	Spatial coordinate in the longitude direction	- (m)

Greek Symbols

σ	Surface tension	mJ/m^2
ε	Amplitude of perturbation	-
ψ	Electrical potential	mJ/m^2
φ	Dielectric constant	-
ξ, τ	Rescaled spatial and time coordinate for long wave approximation	-
λ	Wavenumber of perturbation	-
λ_m	Dominant wavenumber of perturbation	-
λ_{ml}	Nondimensional dominate wavenumber of perturbation	-
λ_n	Neutral wavenumber of perturbation	-
μ	Dynamic viscosity of film fluid	$g/cm.s$
ν	Kinematics viscosity of film fluid	$g/cm.s$
ρ	Density of the film fluid	g/cm^3
γ	Interfacial tension	mJ/m^2
γ^{LW}	The apolar surface tension component	mJ/m^2
γ_y^{LW}	The apolar surface tension component between phases i and j	mJ/m^2
Ω	Magnitude of ion valence	-

ΔG	Excess free energy per unit area due to intermolecular interactions	mJ/m^2
ΔG^{el}	The electrostatic component of free energy	mJ/m^2
$\Delta G^{l,w}$	The apolar component of free energy	mJ/m^2
$\Delta G_{132c}^{l,w}$	Free energy change in bringing two bulk material 1 and 2 from infinity to equilibrium separation distance, d_0 thickness of the thin film	mJ/m^2
ΔG_τ	Total excess free energy per unit area due to intermolecular interactions	mJ/m^2
ΔP	Pressure difference causing the film to thin	kpa
Π	Disjoining pressure	kpa
Γ_m	Dominant wavelength from linear theory	-
Γ_n	Neutral wavelength from linear theory	-
ω	Disturbance growth coefficient	m^3/s
ω_m	Maximum disturbance the growth coefficient	m^3/s
ϕ	First derivative of the excess free energy, ΔG	mJ/m^2
ϕ_h	Second derivative of the excess free energy, ΔG	mJ/m^2